

TITLE: HIGHLY RELIABLE AMORPHOUS HIGH-K GATE OXIDE L02
INVENTORS NAME: Kie Y. Ahn et al.
DOCKET NO.: 1303.026US1

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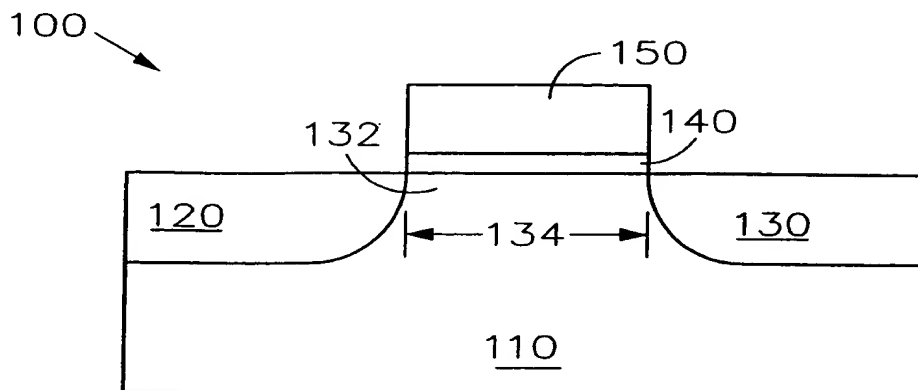


Fig. 1 Prior Art

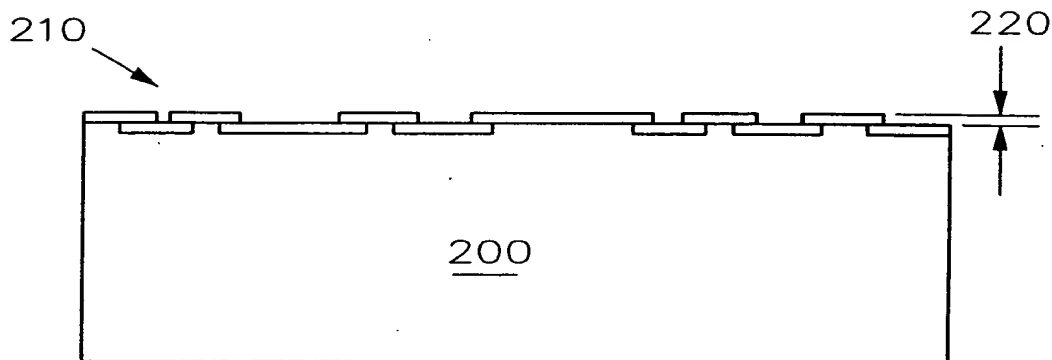


Fig. 2a Prior Art

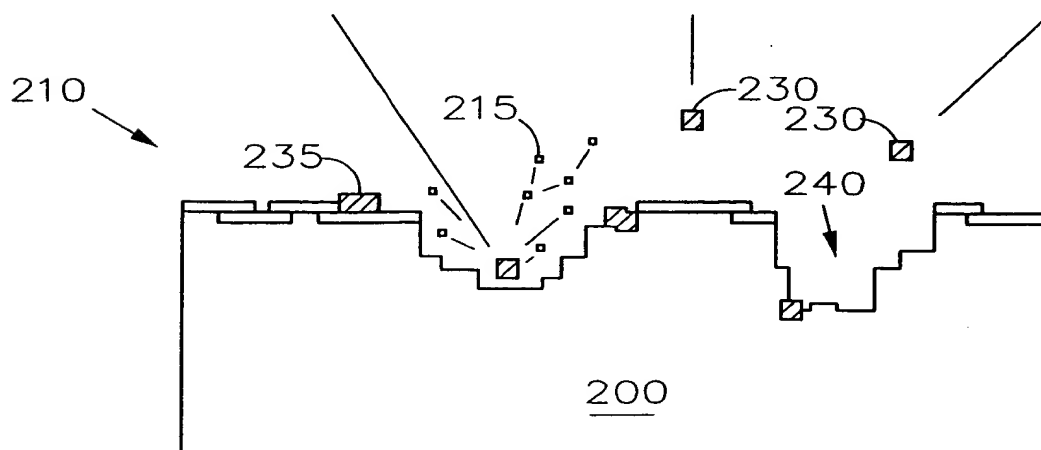


Fig. 2b Prior Art

TITLE: HIGHLY RELIABLE AMORPHOUS HIGH-K GATE OXIDE LAYER
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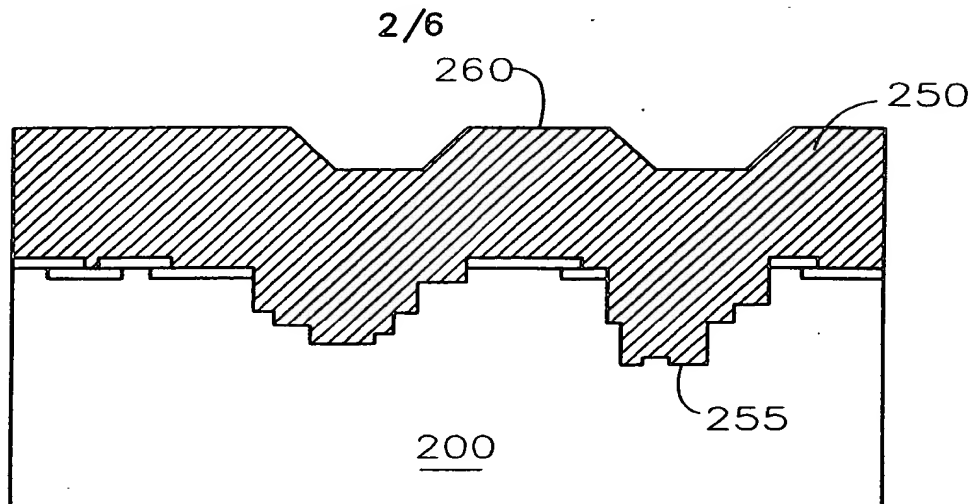


Fig. 2c Prior Art

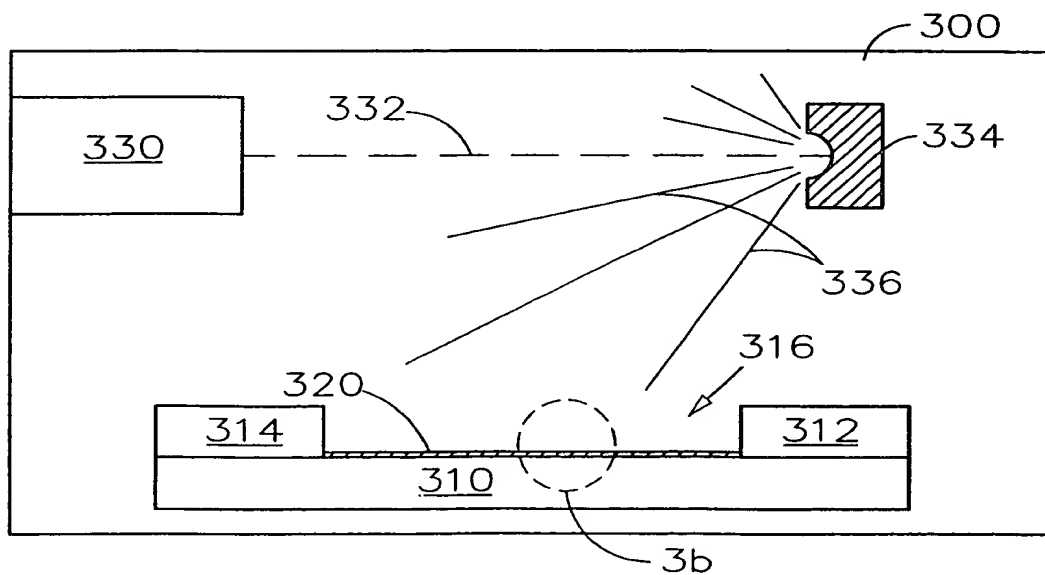


Fig. 3a